

AMENDMENTS TO THE SPECIFICATION

- Please amend the title as follows:

-- Methods for Using Piezoelectric Flow Regulators for Delivering Precursors and Gases for Film Deposition --

- Please replace the Abstract with the following:

Disclosed are methods for using piezoelectric flow regulators for delivering precursors and gases for film deposition. In one embodiment, a method for delivering at least a first and second source chemical into a deposition chamber includes conveying the first source chemical by a first line to a plurality of first piezoelectric flow regulators proximate to first holes in communication with the chamber; conveying the second source chemical by a second line to a plurality of second piezoelectric flow regulators proximate to second holes in communication with the chamber; independently controlling the first flow regulators to control the flow of the first source chemicals to the chamber; and independently controlling the second flow regulators to control the flow of the second source chemicals to the chamber.